



Atty. Dkt. No. 017447-0194

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Koichi WATANABE et al.
Title: SPUTTERING TARGET AND PROCESS FOR PRODUCING Si OXIDE
FILM THEREWITH
Appl. No.: 10/573,406
International Filing Date: 9/22/2004
371(c) Date: 3/27/2006
Examiner: Jason Berman
Art Unit: 1795
Confirmation Number: 2973

AMENDMENT AND REPLY UNDER 37 CFR 1.111

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This communication is responsive to the Non-Final Office Action dated November 13, 2009, concerning the above-referenced patent application.

Applicant has enclosed with this amendment a Petition for Extension of Time to make this response timely.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this document.

Remarks begin on page 4 of this document.

Please amend the application as follows: